

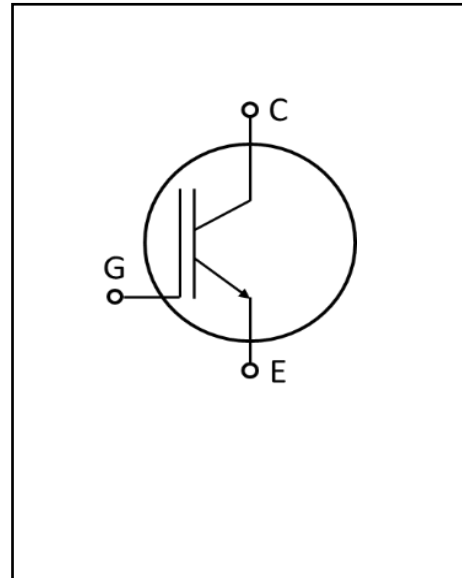
## IGBT Chip

### Features:

- 1200V Trench & Field stop technology
- Low  $V_{cesat}$
- Positive temperature coefficient
- Easy paralleling

### Applications:

- Power drives
- inverter



### Mechanical parameters

Die size	4.20 × 4.20	mm <sup>2</sup>
Emitter pad size	See chip drawing	
Gate pad size	0.98 × 0.79	
Area total	17.64	μm
Thickness	120	
Scribe line Size	80	mm
Wafer size	200	
Max. possible chips per wafer	1545	
Passivation front side	Polyimide	
Pad metal	AlCu with Ti/TiN (5.0μm & 200A/700A)	
Backside metal	Al/Ti/Ni/Ag	

## Maximum Ratings

Parameter	Symbol	Value	Unit
Collector-Emitter voltage	$V_{CE}$	1200	V
DC collector current	$I_C$	15	A
Operating junction temperature	$T_{vj}$	-40 ... +175	°C
Gate emitter voltage	$V_{GE}$	±20	V
Short circuit data	$t_{SC}$	10	µs

## Static Characteristics (tested on wafer), $T_{vj}=25^{\circ}\text{C}$

Parameter	Symbol	Conditions	Value			Unit
			Min.	Typ.	Max.	
Collector-Emitter breakdown voltage	$V_{(BR)CES}$	$V_{GE}=0\text{V}, I_C=1\text{mA}$	1200			V
Collector-Emitter saturation voltage	$V_{CEsat}$	$V_{GE}=15\text{V}, I_C=15\text{A}$		1.80	2.20	
Gate-Emitter threshold voltage	$V_{GE(th)}$	$I_C=0.48\text{mA}, V_{GE}=V_{CE}$	5.2	5.8	6.4	
Zero gate voltage collector current	$I_{CES}$	$V_{CE}=1200\text{V}, V_{GE}=0\text{V}$			10	µA
Gate-Emitter leakage current	$I_{GES}$	$V_{CE}=0\text{V}, V_{GE}=20\text{V}$			100	nA
Integrated gate resistor	$r_G$			None		Ω
Input capacitance	$C_{ies}$	$V_{CE}=25\text{V}, V_{GE}=0\text{V},$ $f=1\text{MHz}$		0.94		nF
Reverse transfer capacitance	$C_{res}$			0.04		

**Chip Drawing**

